

~~WHAT IS CLAIMED IS:~~

~~1. A method of forming a layer member on a substrate, comprising the steps of:~~

~~depositing a first layer on the substrate by a photo CVD process in a reaction chamber; and~~

~~depositing on the first layer by a plasma CVD process in the reaction chamber, a second layer of a material which is the same as or different from the material of the first layer.~~

~~2. A method of forming a layer member on a substrate according to claim 1, further comprising the step of cleaning the reaction chamber by plasma etching before the first layer depositing step or after the second layer depositing step.~~